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O I P E J C A T
MAR 08 2002
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

ATTORNEY'S DKT NO.
015290-546APPLICATION NO.
10/024,208APPLICANT
David J. Cooperberg et alFILING DATE
December 21, 2001GROUP
1763

U.S. PATENT DOCUMENTS

Examiner Initials	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication (MM-DD-YYYY)
	Number	Kind Code (if known)		
JAM	6,052,176		Tuqiang Ni et al	04-18-00
	6,042,687		Vikram Singh et al	03-28-00
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	5,580,385		Ajit P. Paranjpe et al	12-03-96
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Examiner Initials	Foreign Patent Document		Country	Date of Publication (MM-DD-YYYY)	Translation	
	Number	Kind Code (if known)			Yes	no

NON PATENT LITERATURE DOCUMENTS

NON-PATENT LITERATURE DOCUMENTS			
Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		
JAM	ASMUSSEN, JES; "Electron Cyclotron Resonance Microwave Discharges for Etching and Thin-Film Deposition", J. Vac. Sci. Technol. A, Vol. 7, No. 3, May/June 1989, pp. 883-893		
↓	CHAU, T.T. et al; "New Approach to Low Temperature Deposition of High-Quality Thin Films by Electron Cyclotron Resonance Microwave Plasmas", J. Va. Sci. Technol. B 10(5), Sep/Oct 1992, pp. 2170-2178		
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Examiner Signature	Allegando		Date Considered 12/01/02

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. SEND TO: Assistant Commissioner for Patents, Washington, D.C. 20231.

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Examiner Signature	Alexander	Date Considered	12/01/02

(05/01)